ATTY DKT. NO.: AMAT/8629/FEP/GCM/RKK
U.S. SERIAL NO.: Unknown FILED: Herewith
APPLICANT: APPLIED MATERIALS, INC.

TLE: A IV

A Method of Forming a Silicon Oxynitride

Layer

INVENTOR: Christopher Olsen, et al. EXPRESS MAIL No.: EV335470144US

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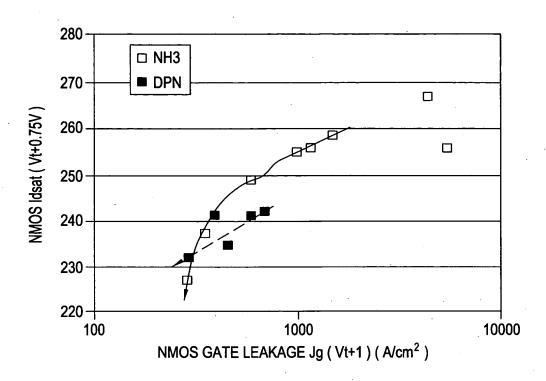


FIG. 1

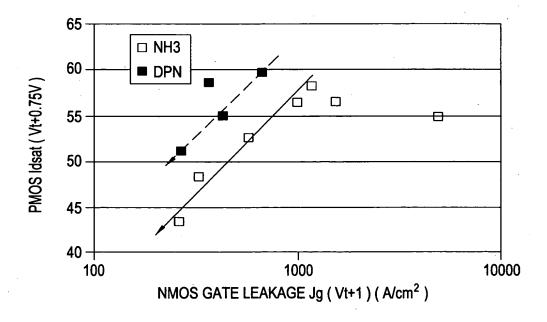


FIG. 2

ATTY DKT. No.: AMAT/8629/FEP/GCM/RKK
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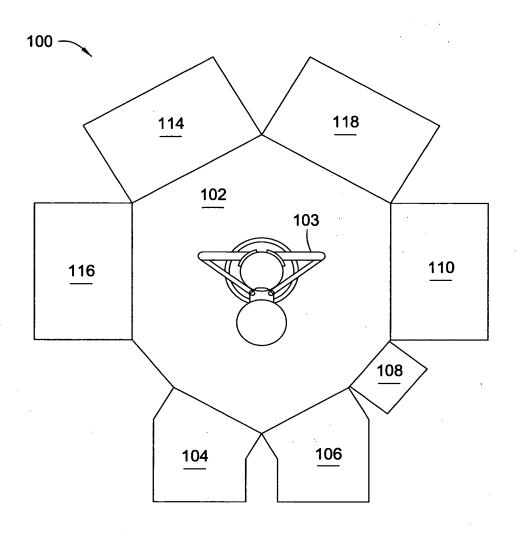


FIG. 3

ATTY DKT. NO.: AMAT/8629/FEP/GCM/RKK U.S. SERIAL NO.: Unknown FILED: Herewith APPLICANT: APPLIED MATERIALS, INC.

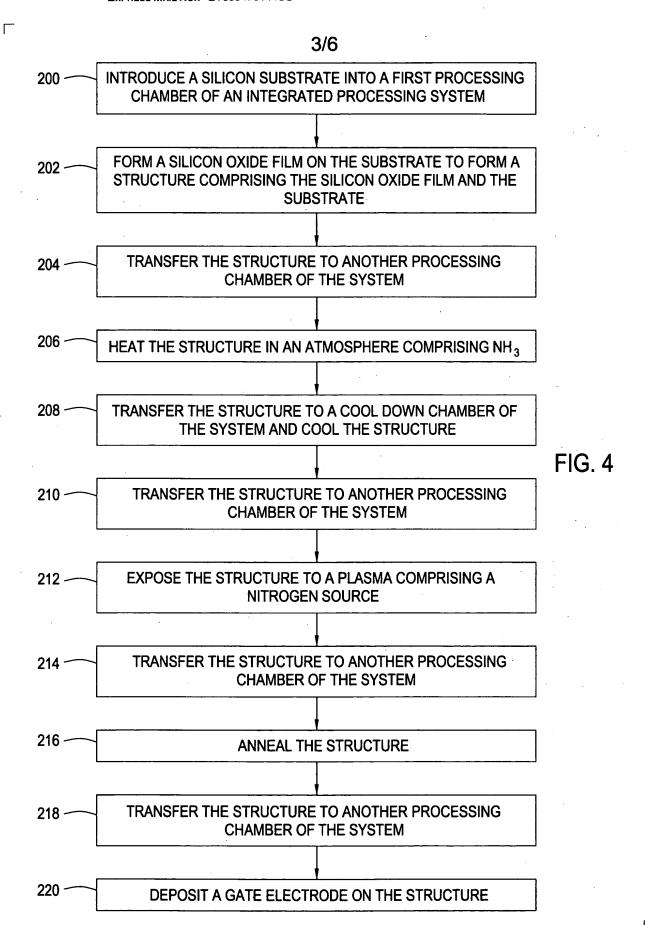
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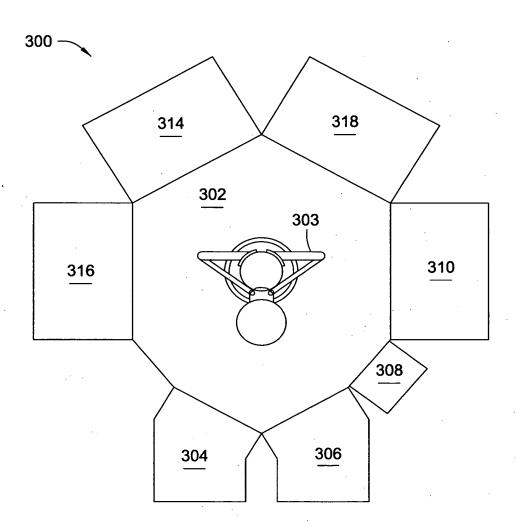


FIG. 5

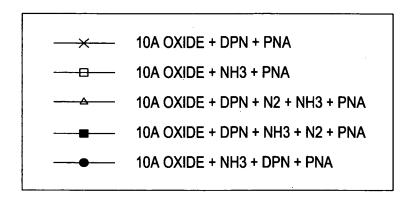
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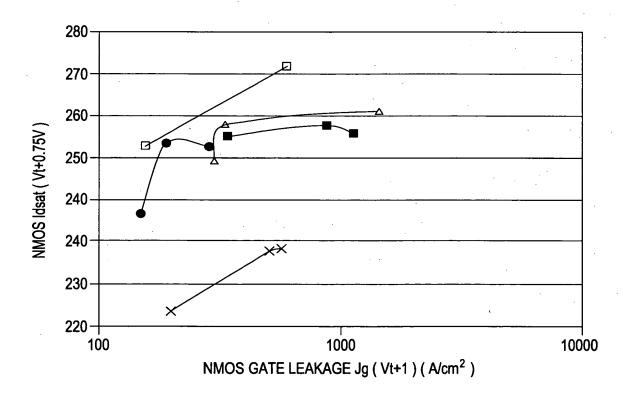


FIG. 6

ATTY DKT. NO.: AMAT/8629/FEP/GCM/RKK U.S. SERIAL NO.: Unknown FILED: Herewith APPLICANT: APPLIED MATERIALS, INC.

TITLE: A N

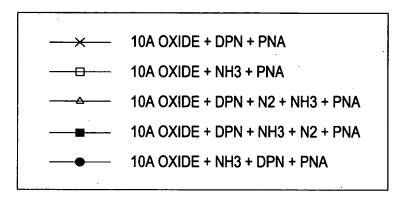
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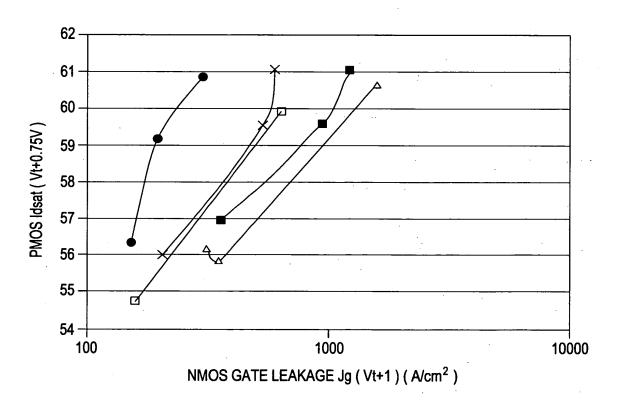


FIG. 7